

IN THE SPECIFICATION

Please insert the following paragraph after paragraph [0019] of the present application:

[0020] Figure 8 shows the elemental composition at various depths of a graded-composition barrier coating of the present invention.

Please renumber the existing paragraphs [0020] to [0045] by incrementing each paragraph number by 1.

Please insert the following paragraph after currently-numbered paragraph [0044]:

[0046] A graded-composition coating having a thickness of about 500 nm was formed on a polycarbonate substrate having a dimension of about 10 cm x 10 cm and a thickness of about 0.2 mm using the RFPECVD technique and tested for water vapor and oxygen transmission. Silane (maximum flow rate of about 500 standard cm³/minute), ammonia (maximum flow rate of about 60 standard cm³/minute), and propylene oxide (maximum flow rate of about 500 standard cm³/minute) were used to produce the graded coating comprising silicon, carbon, oxygen, and nitrogen. The rates of the reactant gases were varied during deposition so that the composition of the coating varied continuously across its thickness. The power fed to the RF electrode was about 100 W when plasma was generated from propylene oxide, and about 200 W when a mixture of silane and ammonia was fed into the reactor. The vacuum level in the reactor was about 0.2 mm Hg and the average temperature was about 55° C. Figure 8 shows the elemental composition

of the coating, as measured by dynamic XPS, as a function of sputtering time to remove portions of the thickness of the coating during the dynamic XPS testing, which is directly related to the depth of the coating.

Please renumber existing currently-numbered paragraph [0045] to [0047].